

A B S T R A C T

AN ION IMPLANTER OPERATING IN PULSED PLASMA MODE

5 The present invention relates to an ion implanter
IMP comprising a pulsed plasma source SPL, a substrate-
carrier tray PPS, and a power supply ALT for the tray.
The implanter also includes a capacitor C connected
10 directly to ground E and connected downstream from the
tray power supply ALT. The invention also provides a
method of using the implanter.

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35 Translation of the title and the abstract as they were when originally filed by the
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38.2, and/or 48.3.